

LABORATÓRIO 3 – FILMES FINOS

DEPOSIÇÃO DE PRATA POR *SPUTTERING*

Tabela 1 - Medições de corrente e tensão para os depósitos de PRATA com 140 nm, 200 nm e 260 nm de espessura.

140 nm		200 nm		260 nm	
I (mA) ±0,001	V (mV) ±0,01	I (mA) ±0,001	V (mV) ±0,01	I (mA) ±0,001	V (mV) ±0,01
1,0	101,8	1,0	15,23	1,0	4,08
1,0	101,3	1,0	14,90	1,0	4,08
2,0	181,3	2,0	29,71	2,0	8,18
2,0	181,2	2,0	29,60	2,0	8,16
3,0	280,4	3,0	43,80	3,0	12,29
3,0	276,2	3,0	43,70	3,0	12,27
4,0	365,0	4,0	58,07	4,0	16,51
4,0	363,0	4,0	57,90	4,0	16,42
5,0	480,0	5,0	72,25	5,0	21,02
5,0	475,0	5,0	71,97	5,0	21,05

Tabela 2 - Médias das medições de corrente e tensão para os depósitos de PRATA com 140 nm, 200 nm e 260 nm de espessura.

140 nm			200 nm			260 nm		
I (mA)	V (mV)	R (Ω)	I (mA)	V (mV)	R (Ω)	I (mA)	V (mV)	R (Ω)
1,0	101,55	101,5	1,0	15,06	15,1	1,0	4,08	4,08
2,0	181,25	90,6	2,0	29,66	14,8	2,0	8,17	4,08
3,0	278,30	92,8	3,0	43,75	14,6	3,0	12,28	4,09
4,0	364,00	91,0	4,0	57,98	14,5	4,0	16,46	4,12
5,0	477,50	95,5	5,0	72,11	14,4	5,0	21,04	4,20